

WE CLAIM:

1. An apparatus comprising:

(a) a substrate including a deposition region and an optional uncoated region, wherein the deposition region includes a level intermediate region disposed between a first end region and a second end region,

wherein the first end region includes a first raised surface portion extending above the level intermediate region and extending circumferentially around the first end region in a continuous manner; and

(b) a dip coated layer over the entire deposition region.

2. The apparatus of claim 1, wherein the substrate is a cylinder.

3. The apparatus of claim 1, wherein the uncoated region is present.

4. The apparatus of claim 1, wherein the first raised surface portion extends above the level intermediate region by a value ranging from about 0.5 to about 1,000 micrometers .

5. The apparatus of claim 1, wherein the first raised surface portion has a triangular shape when viewed in cross section.

6. The apparatus of claim 1, wherein the first raised surface portion has a level top surface.

7. The apparatus of claim 1, wherein the first raised surface portion extends into the uncoated region.

8. The apparatus of claim 1, wherein the dip coated layer comprises a charge transport material.

9. The apparatus of claim 1, wherein the portion of the dip coated layer over the intermediate region has a substantially uniform thickness.

1 10. The apparatus of claim 1, wherein the second end region includes a second
2 raised surface portion extending above the level intermediate region and extending
3 circumferentially around the second end region in a continuous manner.
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5 11. An apparatus comprising:

6 (a) a substrate defining a longitudinal axis and including a deposition region
7 and an optional uncoated region, wherein the deposition region includes a level
8 intermediate region disposed between a first end region and a second end region,

9 wherein the first end region includes a plurality of raised surface portions, each
10 of the raised surface portions extending above the level intermediate region and
11 extending only partially around the first end region, wherein the plurality of the raised
12 surface portions, when viewed at a substrate end view, collectively extend
13 circumferentially around the first end region in a continuous manner; and

14 (b) a dip coated layer over the entire deposition region.
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16 12. The apparatus of claim 11, wherein the plurality of the raised surface
17 portions ranges in number from 2 to 5.
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19 13. A coating method comprising:

20 (a) providing a substrate including a deposition region and an optional uncoated
21 region, wherein the deposition region includes a level intermediate region disposed
22 between a first end region and a second end region,

23 wherein the first end region includes a first raised surface portion extending
24 above the level intermediate region and extending circumferentially around the first end
25 region in a continuous manner; and

26 (b) dip coating a layer of a coating solution over the entire deposition region.
27

28 14. The coating method of claim 13, wherein the substrate is a cylinder.
29

30 15. The coating method of claim 13, wherein the first raised surface portion
31 extends above the level intermediate region by a value ranging from about 0.5 to about
32 1,000 micrometers .
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34 16. The coating method of claim 13, wherein the first raised surface portion has
35 a triangular shape when viewed in cross section.

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2 17. The coating method of claim 13, wherein the first raised surface portion has
3 a level top surface.
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5 18. The coating method of claim 13, wherein the first raised surface portion
6 extends into the uncoated region.
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8 19. The coating method of claim 13, wherein the dip coated layer comprises a
9 charge transport material.
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11 20. The coating method of claim 13, wherein the portion of the dip coated layer
12 over the intermediate region has a substantially uniform thickness.